

ABSTRACT

An apparatus **115** for processing a substrate **20**, comprises an integrated pumping system **155** having a high operating efficiency, small size, and low vibrational and noise levels. The apparatus **115** comprises a chamber, such as a load-lock chamber **110**, transfer chamber **115**, or process chamber **120**. An integrated and local pump **165** is abutting or adjacent to one of the chambers **110**, **115**, **120** for evacuating gas from the chambers. The pump has an inlet **170** connected to a chamber **110**, **115**, **120**, and an outlet **175** that exhausts the gas to atmospheric pressure. Preferably, the pump **165** comprises a pre-vacuum pump or a low vacuum pump.